

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently amended) A plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein the protective layer ~~includes~~ is made of magnesium oxide including carbon and silicon.

2. (Original) A plasma display panel as claimed in claim 1, wherein a protective layer is made of magnesium oxide including silicon with 5×10^{18} atoms/cm³ to 2×10^{21} atoms/cm³, and carbon with 1×10^{18} atoms/cm³ to 2×10^{21} atoms/cm³.

3. (Original) A plasma display panel as claimed in claim 2, wherein the number of carbon atoms is greater than that of silicon.

4. (Currently amended) A method of manufacturing a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer made of magnesium oxide including carbon and silicon is formed on the dielectric layer, wherein a process for forming the protective layer is a process ~~for forming a film~~ using a material for a protective layer, including carbon, and silicon and magnesium oxide.

5. (Currently amended) A method of manufacturing a plasma display panel as claimed in claim 4, wherein ~~[[a]] the material for a protective layer is magnesium oxide including carbon and silicon; wherein~~ includes the density of carbon ranges from 5 ppm to 1,500 ppm by weight~~[[:]]~~, and ~~wherein~~ the density of silicon ranges from 7 ppm to 8,000 ppm by weight.

6. (Currently amended) A method of manufacturing a plasma display panel as claimed in claim 4, wherein ~~[[a]] the material for a protective layer is~~ includes magnesium oxide ~~including and~~ silicon carbide; and wherein the density of silicon carbide ranges from 40 ppm to 12,000 ppm by weight.

7. (Currently amended) A method of manufacturing a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain

electrode formed on a substrate, and in which a protective layer made of magnesium oxide including carbon and silicon is formed on the dielectric layer, wherein carbon and silicon are added in the protective layer after the protective layer is formed by forming magnesium oxide on the dielectric layer.

8. (Currently amended) A material for a protective layer of a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer made of magnesium oxide including silicon and carbon is formed on the dielectric layer, wherein the material for a protective layer includes carbon, and silicon and magnesium oxide.

9. (Currently amended) A material for a protective layer of a plasma display panel as claimed in claim 8, wherein ~~[[a]] the material for a protective layer is made of magnesium oxide including carbon and silicon; wherein~~ includes the density of the carbon ranges from 5 ppm to 1,500 ppm by weight~~[[;]]~~, and ~~wherein~~ the density of the silicon ranges from 7 ppm to 8,000 ppm by weight.

10. (Currently amended) A material for a protective layer of a plasma display panel as claimed in claim 8, wherein ~~[[a]] the material for a protective layer is made of~~ includes magnesium oxide ~~including~~ and silicon carbide; and wherein the density of the silicon carbide ranges from 40 ppm to 12,000 ppm by weight.